



Patent  
Attorney's Docket No. 015290-458

1773  
\$

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of )  
 )  
Christopher C. CHANG et al. ) Group Art Unit: 1773  
 )  
Application No.: 09/749,917 ) Examiner: N. Uhler  
 )  
Filed: December 29, 2000 ) Confirmation No.: 6832  
 )  
For: LOW CONTAMINATION PLASMA )  
CHAMBER COMPONENTS AND )  
METHODS FOR MAKING THE SAME )

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AUG 26 2002  
TC 1700

AMENDMENT/REPLY TRANSMITTAL LETTER

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Enclosed is a reply for the above-identified patent application.

- ☐ A Petition for Extension of Time is also enclosed.
- ☐ A Terminal Disclaimer and a check for ☐ \$55.00 (248) ☐ \$110.00 (148) to cover the requisite Government fee are also enclosed.
- ☐ Also enclosed is \_\_\_\_\_.
- ☐ Small entity status is hereby claimed.
- ☐ Applicant(s) request continued examination under 37 C.F.R. § 1.114 and enclose the ☐ \$370.00 (279) ☐ \$740.00 (179) fee due under 37 C.F.R. § 1.17(e).
- ☐ Applicant(s) previously submitted \_\_, on \_\_, for which continued examination is requested.
- ☐ Applicant(s) request suspension of action by the Office until at least \_\_, which does not exceed three months from the filing of this RCE, in accordance with 37 C.F.R. § 1.103(c). The required fee under 37 C.F.R. § 1.17(i) is enclosed.
- ☐ A Request for Entry and Consideration of Submission under 37 C.F.R. § 1.129(a) (146/246) is also enclosed.
- ☐ No additional claim fee is required.

☒ An additional claim fee is required, and is calculated as shown below:

| AMENDED CLAIMS   |               |   |              |                   |                 |
|--|---------------|---|--------------|-------------------|-----------------|
|  | NO. OF CLAIMS | HIGHEST NO. OF CLAIMS PREVIOUSLY PAID FOR | EXTRA CLAIMS | RATE              | ADDT'L FEE      |
| Total Claims   | 34            | MINUS 34 =                                | -0-          | × \$18.00 (103) = | --              |
| Independent Claims   | 5             | MINUS 3 =                                 | 2            | × \$84.00 (102) = | \$168.00        |
| If Amendment adds multiple dependent claims, add \$280.00 (104)        |               |   |              |                   | --              |
| Total Amendment Fee  |               |   |              |                   | \$168.00        |
| If small entity status is claimed, subtract 50% of Total Amendment Fee |               |   |              |                   | --              |
| <b>TOTAL ADDITIONAL FEE DUE FOR THIS AMENDMENT</b>                     |               |   |              |                   | <b>\$168.00</b> |

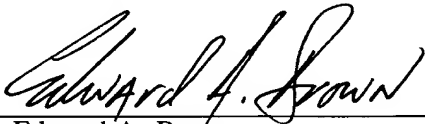
☐ A claim fee in the amount of \$\_\_\_\_\_ is enclosed.

☒ Charge \$ 168.00 to Deposit Account No. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17, 1.20(d) and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

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By:   
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Date: August 22, 2002



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Group Art Unit: 1773 ✓  
Examiner: N. Uhler ✓  
Confirmation No.: 6832

**AMENDMENT**

Assistant Commissioner for Patents  
Washington, D.C. 20231

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Sir:

In response to the Official Action dated May 22, 2002, please amend the above-identified application as follows.

**IN THE CLAIMS:**

Please replace Claims 21 and 23 as follows:

21. (Amended) A component of a plasma reactor, the component having one or more surfaces exposed to the plasma during processing, the component comprising an as-sprayed plasma sprayed coating on a plasma exposed surface of the component, the component and the coating both comprising the same ceramic material selected from the group consisting of alumina, yttria, zirconia, silicon carbide, silicon nitride, boron carbide and boron nitride, and the coating having an as-sprayed surface roughness that promotes the adhesion of polymer deposits.

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